

Photomask Japan 2020

The 27th Symposium on Photomask and NGL Mask Technology

April 19(Sun.) - 21(Tue.), 2020

- Special Event on Sunday,
- Main Symposium on Monday - Tuesday

Symposium Chair:

Takeo Watanabe

University of Hyogo

Abstract Due Date:
November 29, 2019

Manuscript Due Date:
March 31, 2020

Detailed information will be announced at the 2nd Call for Papers. Manuscripts are required of all accepted applicants and must be submitted in English.

Organized by



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For more information, contact:
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Photomask Japan 2020 is the 27th international symposium on photomasks and NGL masks in Japan. The aim of the symposium is to bring together engineers and investigators from Japan, USA, and all over the world in the field of photomasks, NGL masks, and related technologies to discuss recent progress, applications, and future trends. The symposium program will feature invited papers, contributed papers, poster sessions, and a rump session with panel discussion. Display opportunities will be provided to mask manufacturing materials, and equipment companies.

Papers are solicited on the following and related topics:

- **Materials for Photomasks**
- **Fabrication Process Steps and Equipment for Photomasks (developing, etching, cleaning etc.)**
- **Photomask Writing Tools and Technologies including multi-beam EB writer**
- **Tools and Technologies for Metrology/ Inspection/ Repair**
- **Technologies and infrastructures for EUVL/ NIL/ FPD masks**
- **Mask Data Preparations, EDA and DTCO**
- **Photomasks with RET: PSM, OPC, SMO and Multiple Patterning**
- **Photomask-related Lithography Technologies**
- **DSA (Directed Self-Assembly) related mask technologies**
- **Strategies and Business Challenges: Cost, Cycle-Time, ML2 etc.**
- **Mask/ Lithography related Technology in Academia (Poster Session)**
- **Patterning technology for semiconductor and electronic devices**
- **Semiconductor manufacturing technologies**
- **EB direct writing, EB lithography technologies**

Abstract Submissions

All authors are *strongly encouraged* to submit their abstract by the due date, November 29 2019 via the PMJ official website. Abstract submission Web page will be opened from October 2019 at:

<http://www.photomask-japan.org/>

Further information and instruction will be available from 2nd Announcement & Call for Papers, which will be published around September, 2019

***Please do not send the abstract by e-mail or FAX.**

Symposium Site

Symposium site of Photomask Japan 2020 will be "Annex Hall" at Pacifico Yokohama